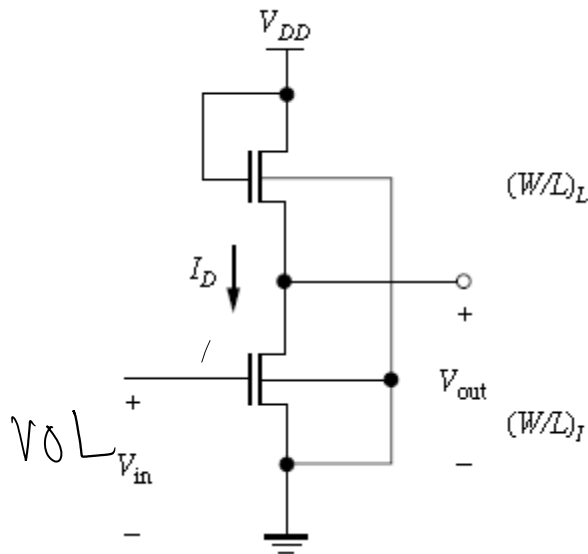

ELEC 402

Design of CMOS Inverter (Noise-margin-centric approach) Lecture 7

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Slides Courtesy : Dr. Res Saleh (UBC), Dr. D. Sengupta (AMD), Prof. B. Razavi (UCLA)

Saturated-enhancement-load Inverter



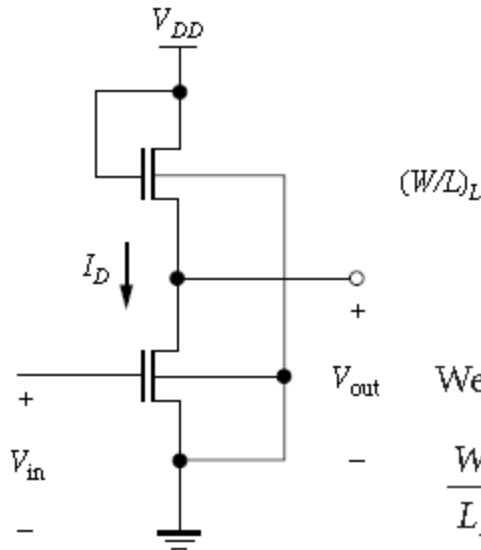
To alleviate the area problem we replace the resistor
With a diode-connected transistor (always in saturation)
This performance of this logic gate is affected by the ratio
Of devices, hence called *ratioed* inverter

$$K_R = \frac{k_{\text{invert}}}{k_{\text{load}}} = \frac{k' (W/L)_I}{k' (W/L)_L} = \frac{(W/L)_I}{(W/L)_L}$$

The output voltage does not quite reach V_{DD}
(The Load device requires at least V_T drop on its V_{GS})

$$\begin{aligned} V_{OH} &= V_{DD} - V_T(V_{OH}) \\ &= V_{DD} - [V_{T0} + \gamma(\sqrt{V_{OH} + 2|\phi_F|} - \sqrt{2|\phi_F|})] \end{aligned}$$

Saturated-enhancement-load Inverter – cont'd



To derive the V_{OL} again it is important to find the proper region of operation for each transistor

$$I_{Df}(\text{lin}) = I_{DL}(\text{sat})$$

We can substitute in the current equations to obtain

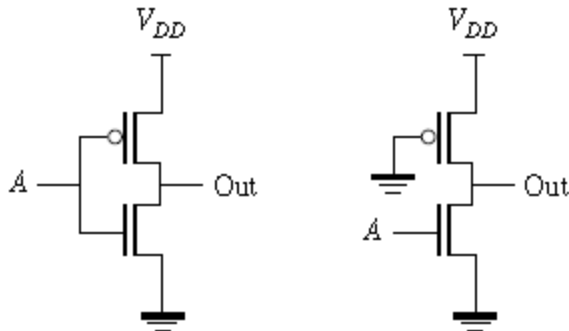
$$\frac{W_f}{L_f} \frac{\mu_n C_{ox}}{\left(1 + \frac{V_{out}}{E_{CN} L_f}\right)} \left[(V_{in} - V_{Tf}) V_{out} - \frac{V_{out}^2}{2} \right] = \frac{W_L \mu_{sat} C_{ox} (V_{DD} - V_{out} - V_{TL})^2}{(V_{DD} - V_{out} - V_{TL}) + E_{CN} L_L}$$

Note that V_{in} should be the output of previous stage (ideally $V_{DD} - V_T$), however, to keep Things simple we occasionally assume $V_{in} = V_{DD}$

Pseudo-NMOS Inverter

To address issues with NMOS loads

- Saturated NMOS load, a.k.a diode connected load, has degraded V_{OH}
- Linear NMOS load requires two supplies and extra area/interconnects
- CMOS gates require multiple loads for multi fanin inputs (?)



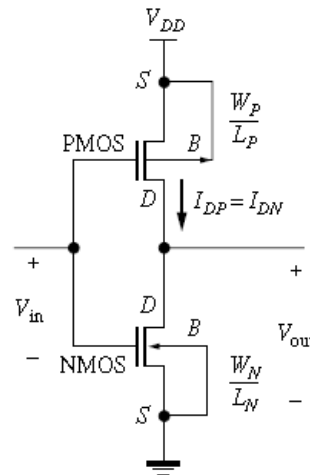
Solves the abovementioned problems, However

- *Ratioed* inverter, i.e. V_{OL} a function of two device ratios
- Large T_{PLH} (why?)

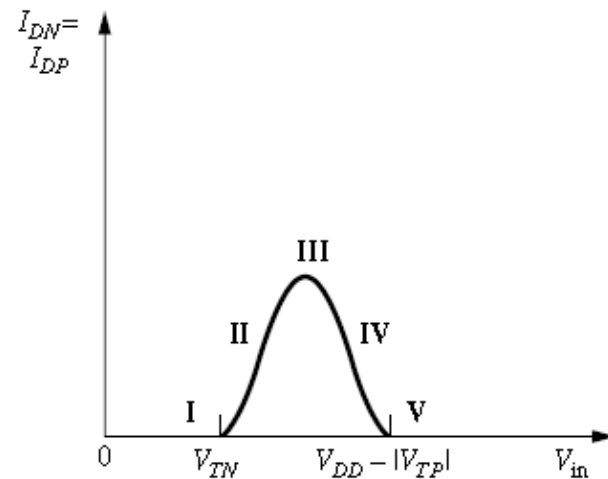
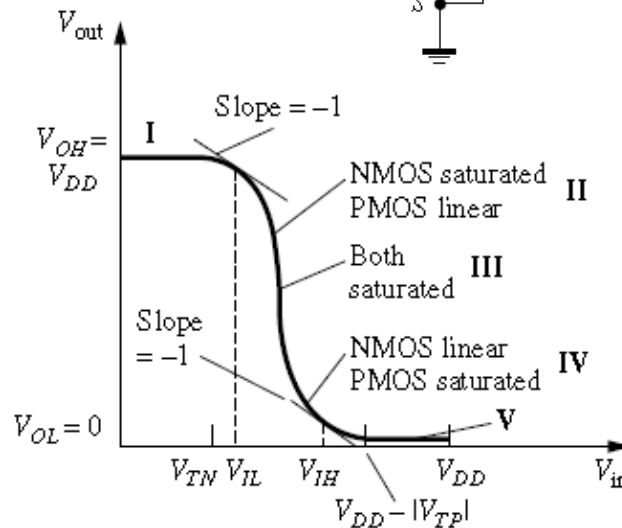
$$I_{DP}(\text{sat}) = I_{DN}(\text{lin})$$

$$\frac{W_P \mu_{\text{sat}} C_{ox} (V_{DD} - |V_{TP}|)^2}{(V_{DD} - |V_{TP}|) + E_{CP} L_P} = \frac{W_N}{L_N} \frac{\mu_n C_{ox}}{\left(1 + \frac{V_{OL}}{E_{CN} L_N}\right)} \left[(V_{DD} - V_{TN})(V_{OL}) - \frac{(V_{OL})^2}{2} \right] \Rightarrow V_{OL} = \frac{I_{DP}(\text{sat})}{k_N (V_{DD} - V_{TN})}$$

CMOS Inverter



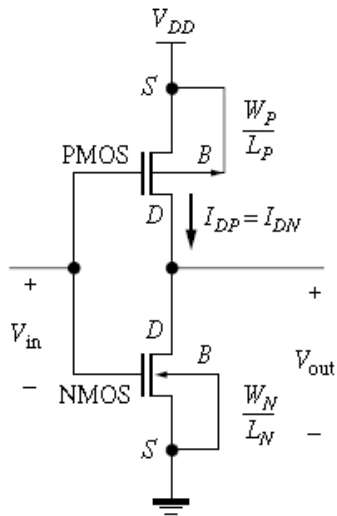
- Address both issues of area and static power consumption
- Load that is complementary to the inverting device
- 5 distinct regions of operation can be detected



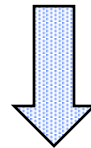
CMOS Inverter

Region II: NMOS saturation, PMOS Linear

V_{IL} falls in this region (why?)



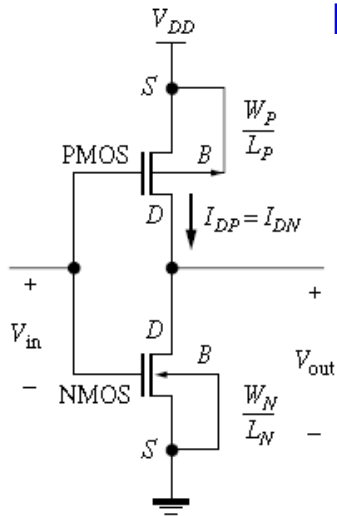
$$\frac{W_N \mu_{\text{sat}} C_{\text{ox}} (V_{\text{in}} - V_{\text{TN}})^2}{(V_{\text{in}} - V_{\text{TN}}) + E_{\text{CN}} L_N} = \frac{W_P}{L_P} \frac{\mu_p C_{\text{ox}}}{\left(1 + \frac{V_{\text{DD}} - V_{\text{out}}}{E_{\text{CP}} L_P}\right)} \times \left[(V_{\text{DD}} - V_{\text{in}} - |V_{\text{TP}}|)(V_{\text{DD}} - V_{\text{out}}) - \frac{(V_{\text{DD}} - V_{\text{out}})^2}{2} \right]$$



$$V_{\text{IL}} = \frac{2V_{\text{out}} - V_{\text{DD}} - |V_{\text{TP}}| + (k_N/k_P)(V_{\text{TN}})}{1 + (k_N/k_P)}$$

CMOS Inverter – Switching Point

Region III: NMOS saturation, PMOS saturation



V_S falls in this region (why?)

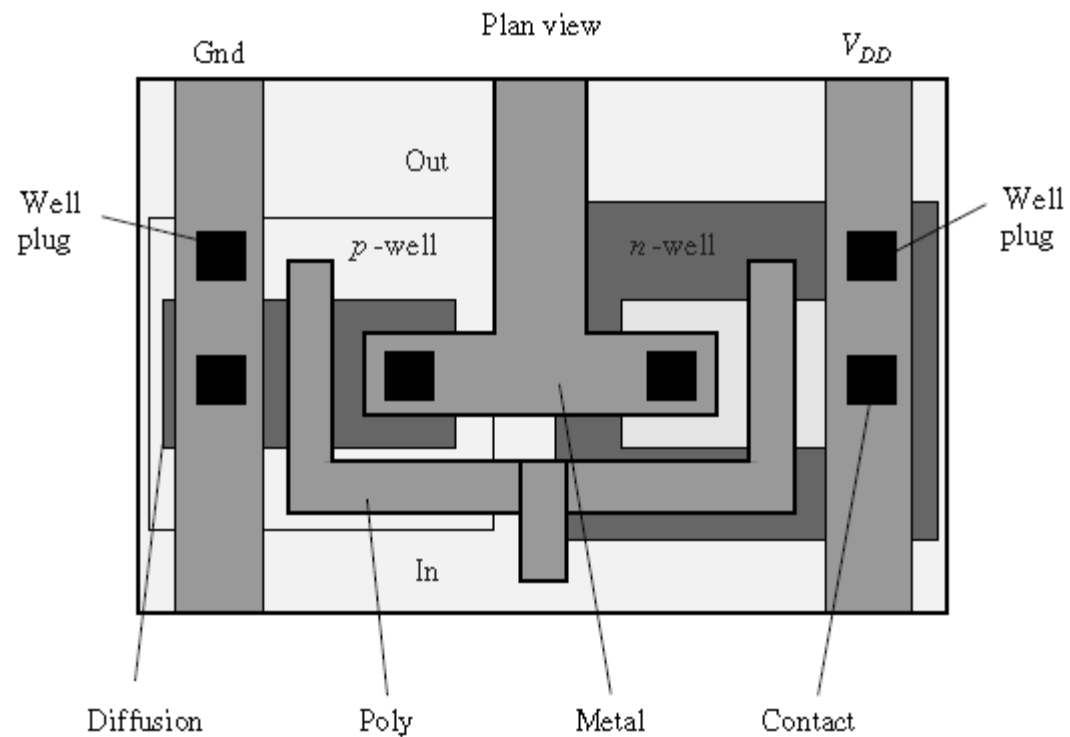
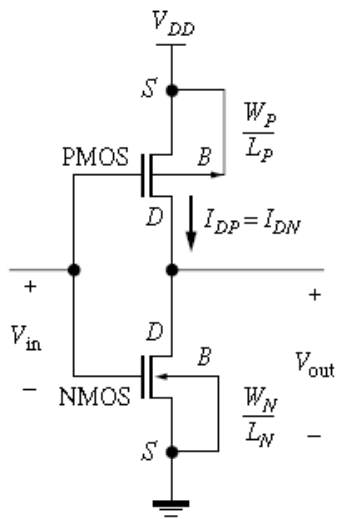
$$\frac{W_N \mu_{sat} C_{ox} (V_S - V_{TN})^2}{(V_S - V_{TN}) + E_{CN} L_N} = \frac{W_P \mu_{sat} C_{ox} (V_{DD} - V_S - |V_{TP}|)^2}{(V_{DD} - V_S - |V_{TP}|) + E_{CP} L_P}$$

(Board Discussion)

$$V_S = \frac{V_{DD} - |V_{TP}| + \chi V_{TN}}{1 + \chi}$$

$$\chi = \sqrt{\frac{\frac{W_N}{E_{CN} L_N}}{\frac{W_P}{E_{CP} L_P}}} = \sqrt{\frac{\mu_n W_N}{\mu_p W_P}}$$



















CMOS Inverter - Layout



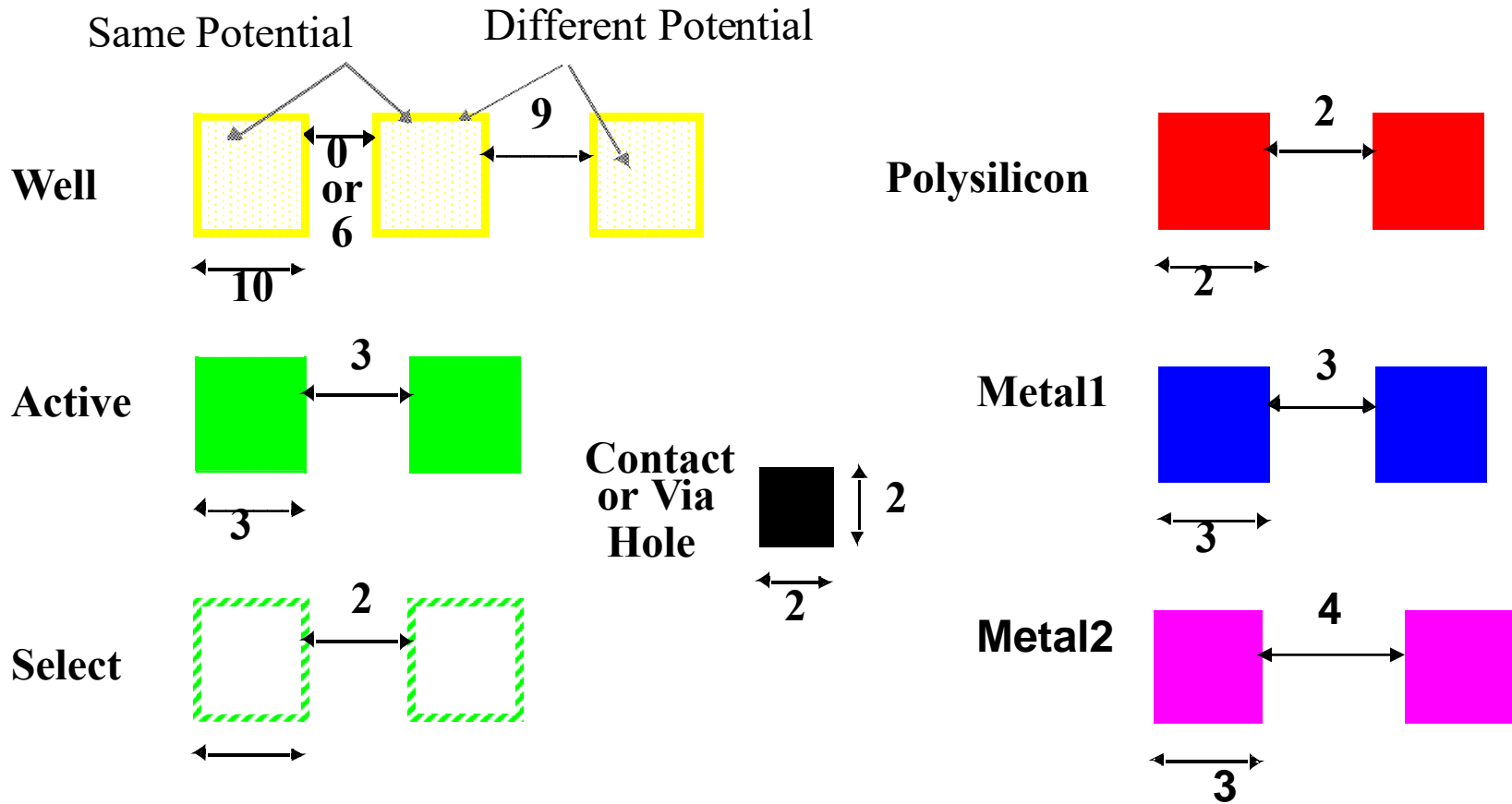
Note Minimum size, well-plugs, design rules

Design Rules

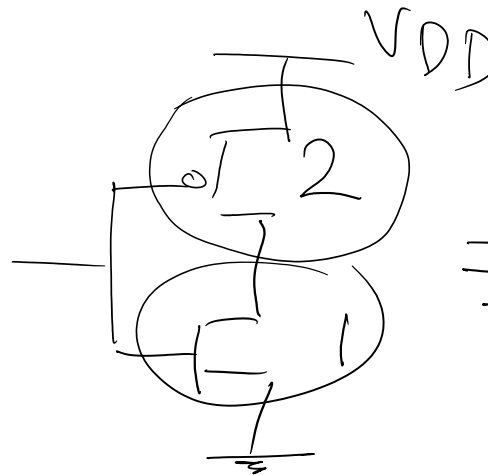
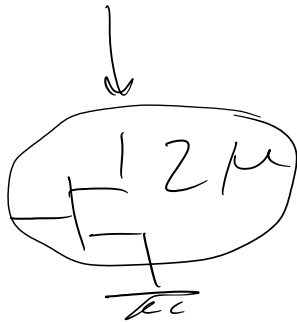
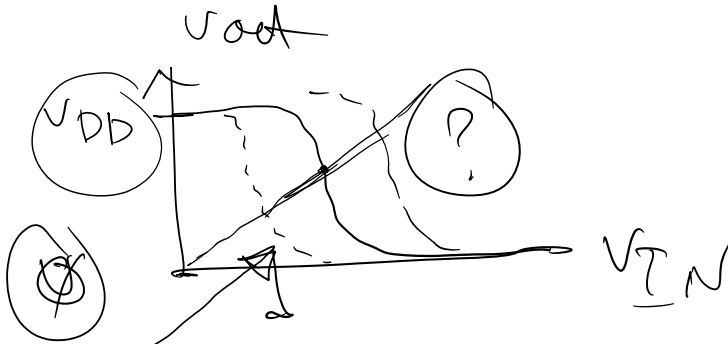
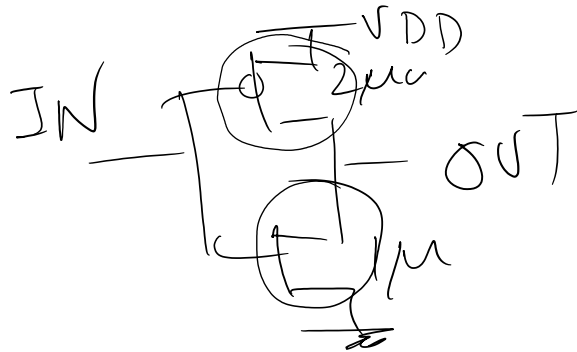
- Interface between designer and process engineer
- Guidelines for constructing process masks
- Unit dimension: Minimum line width
 - scalable design rules: lambda parameter
 - absolute dimensions (micron rules)

Layer Description	Representation				
metal	 m1	 m2	 m3	 m4	 m5
well	 nw				
polysilicon	 poly				
contacts & vias	 ct	 v12,v23,v34,v45	 nwc	 pwc	
active area and FETs	 ndif	 pdif	 nfet	 pfet	
select	 nplus	 pplus	 prb		

DRC Rules - II



$$I_P = I_N \Rightarrow W_N \neq \cancel{M_P} \quad \begin{matrix} \textcircled{M_P} \\ \textcircled{M_N'} \end{matrix}$$



\neq

